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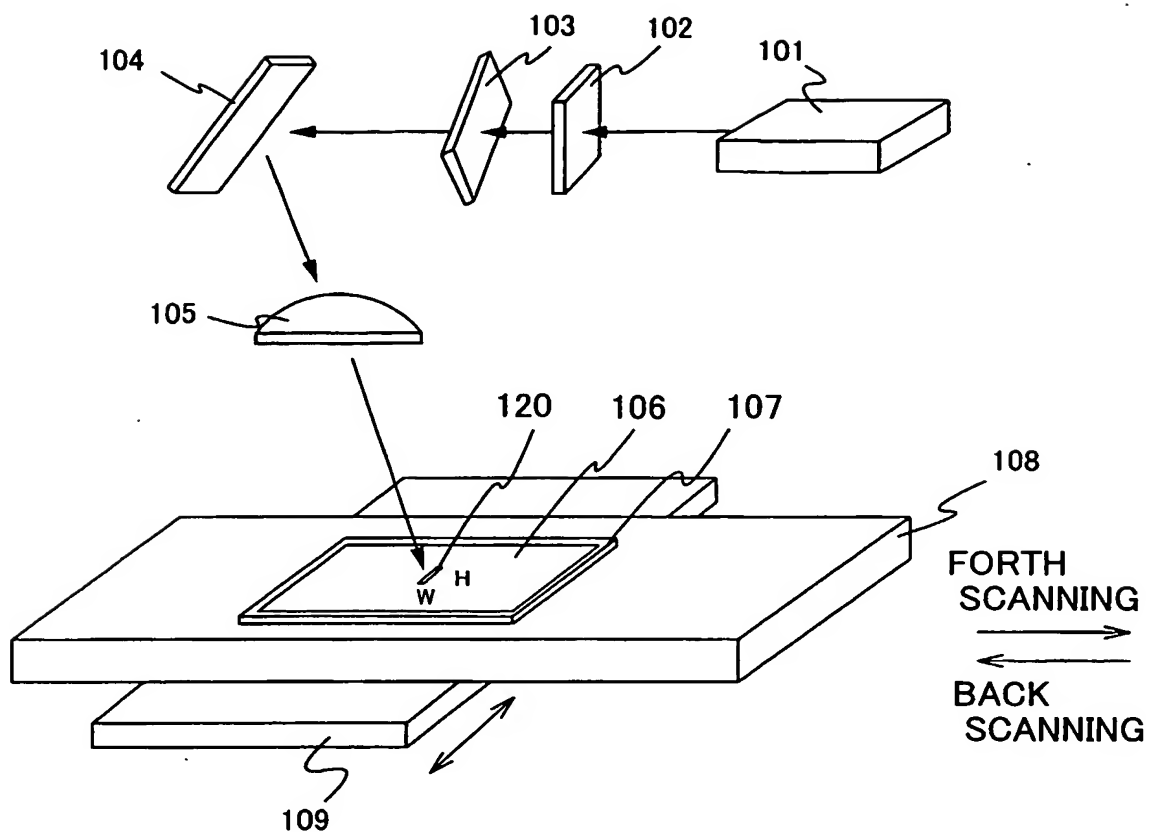


FIG. 1

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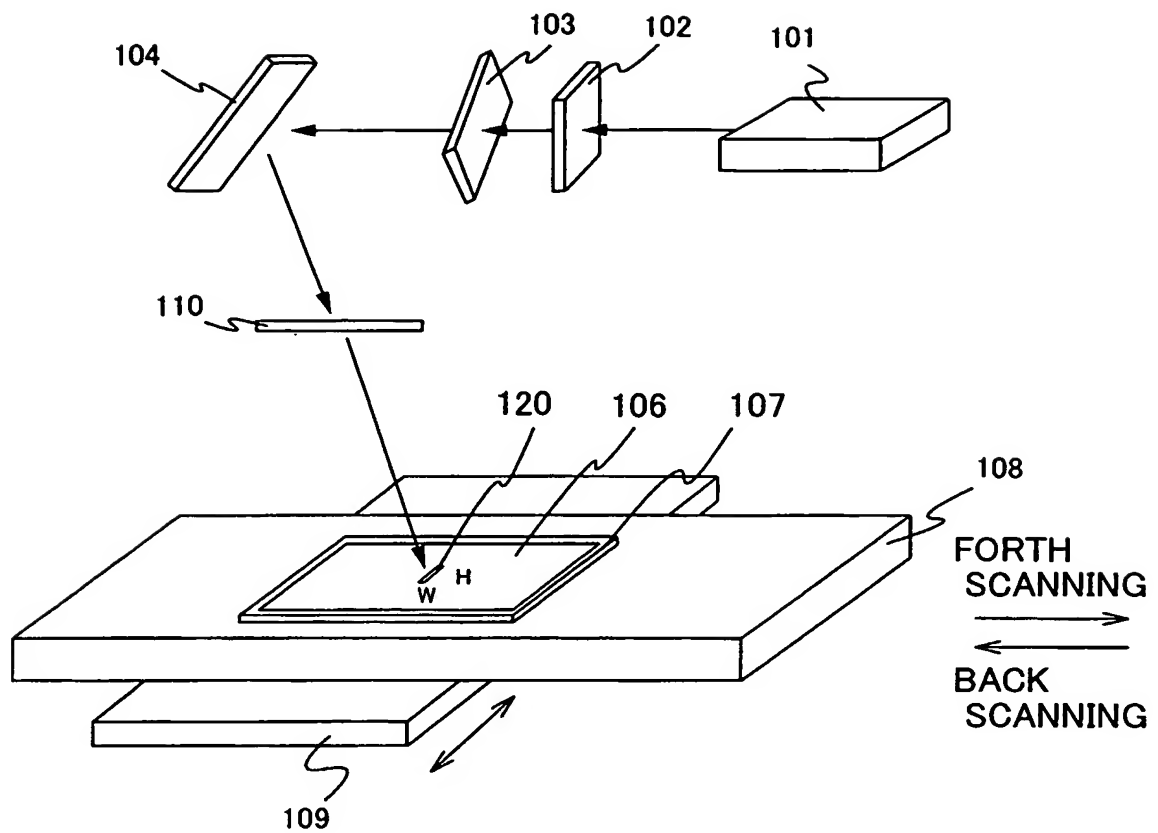


FIG. 2

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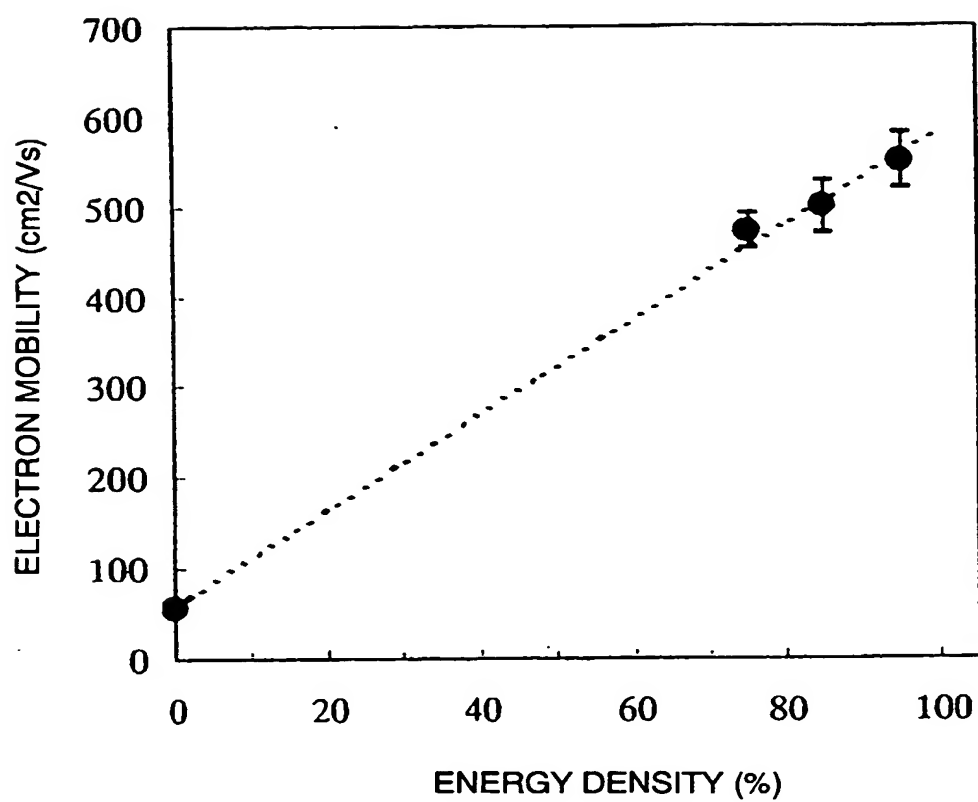


FIG. 3

ELECTRON MOBILITY vs. ENERGY DENSITY of N-ch TFT

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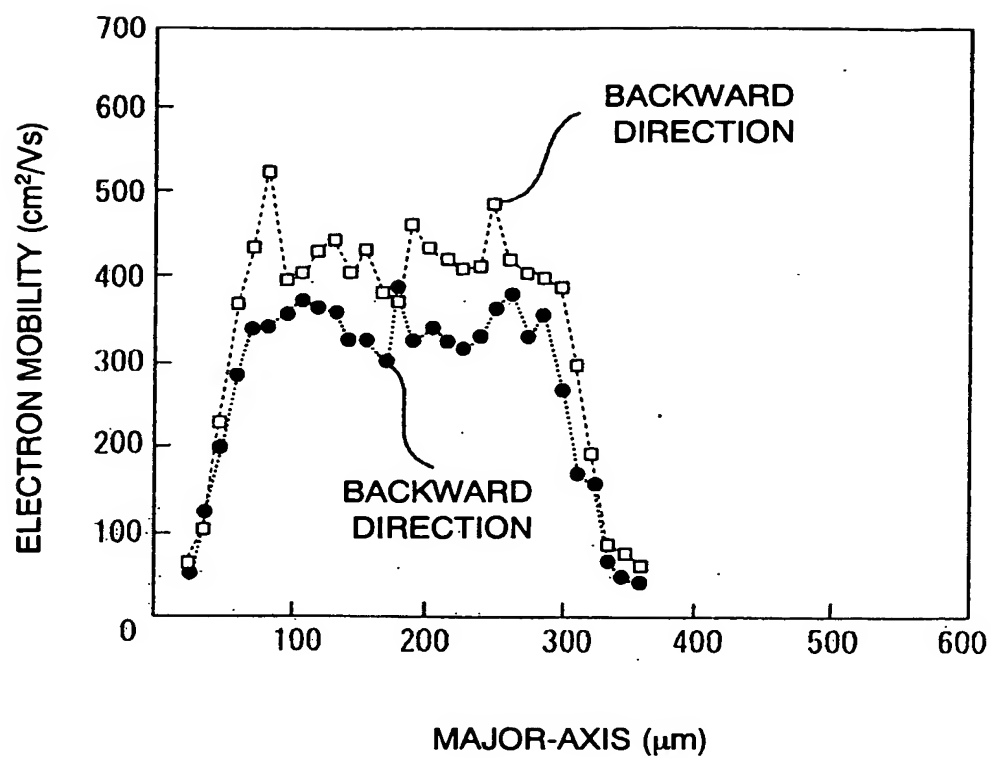


FIG. 4 ELECTRON MOBILITY DISTRIBUTION of N-ch TFT

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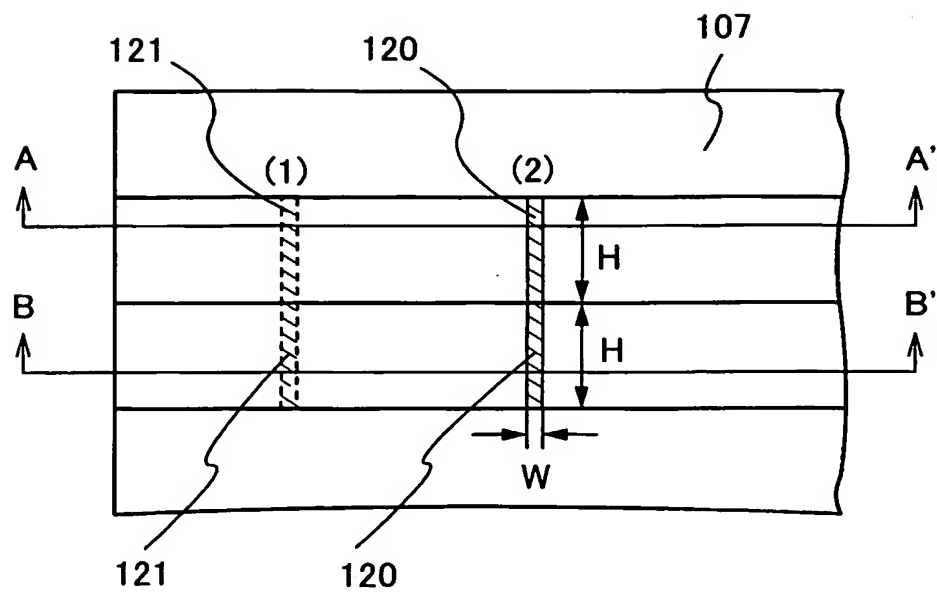


FIG. 5

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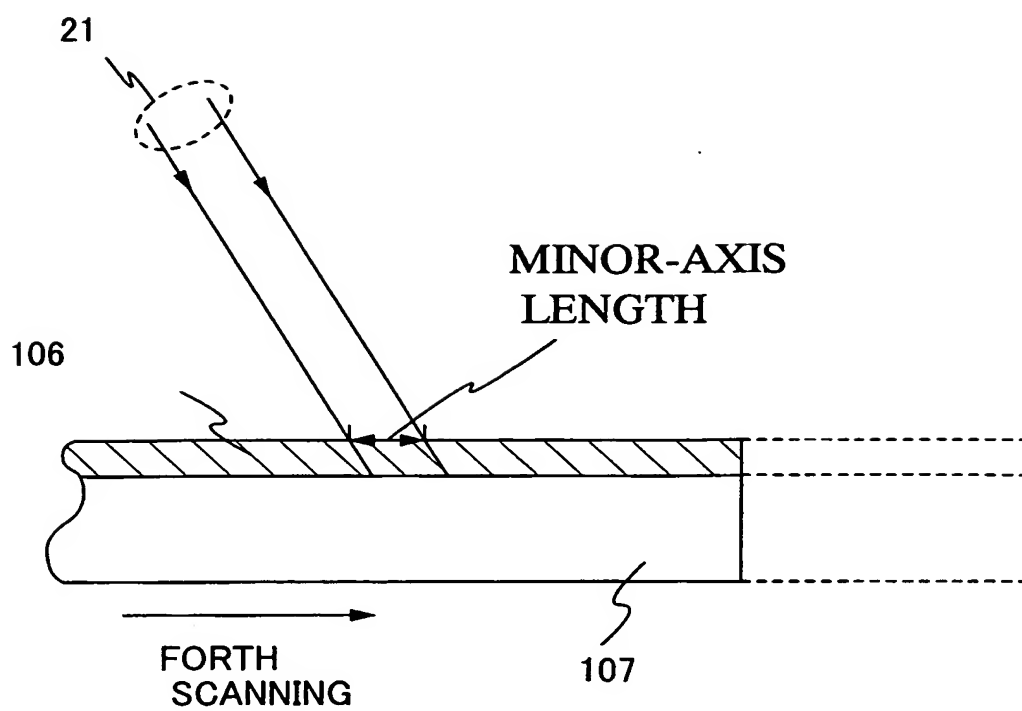


FIG. 6

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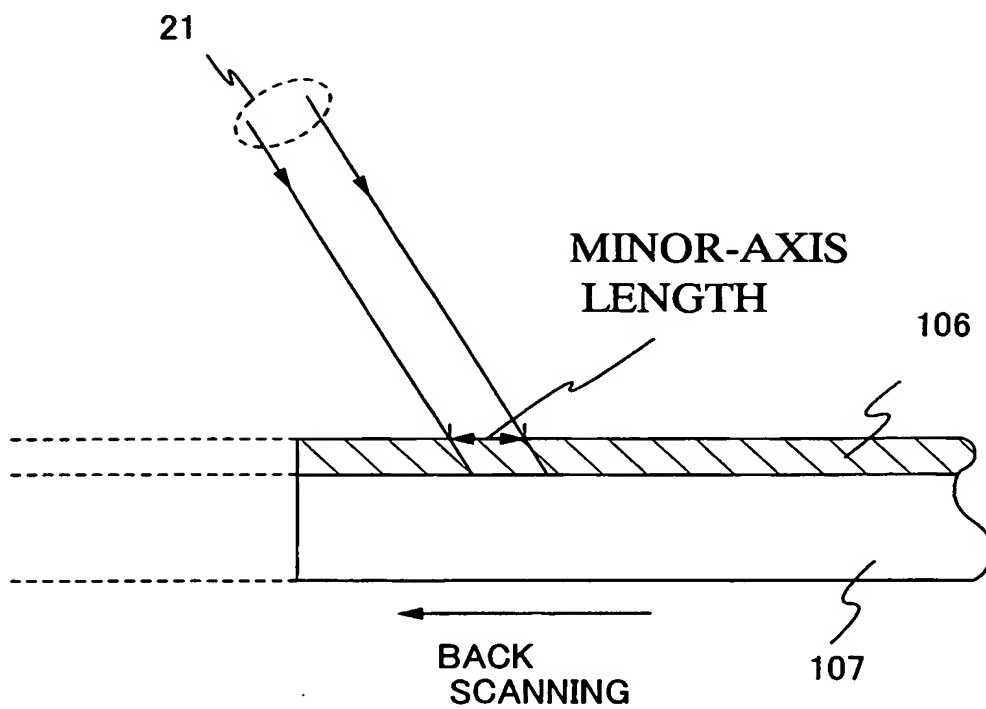


FIG. 7

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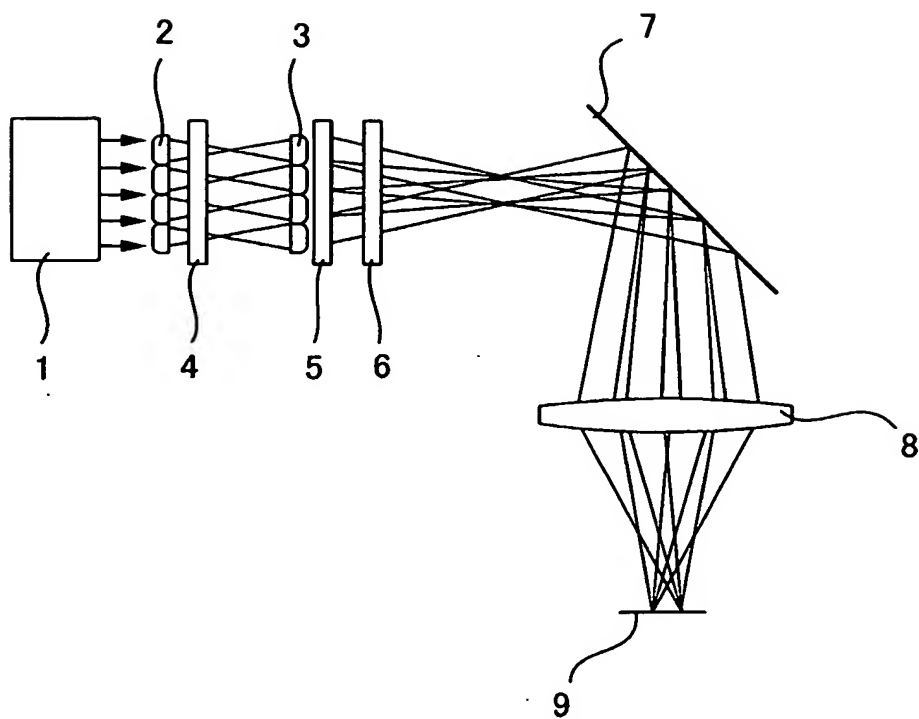


FIG. 8



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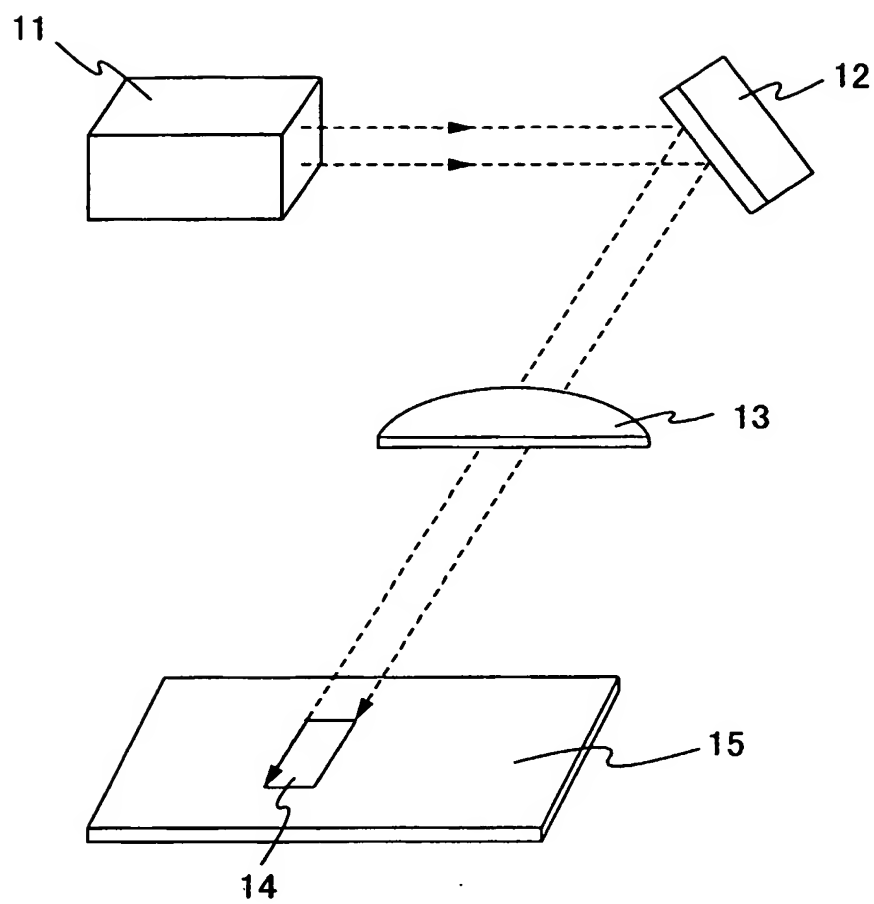


FIG. 9

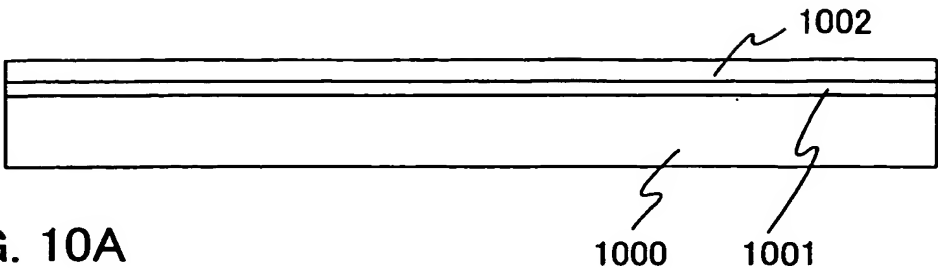


FIG. 10A

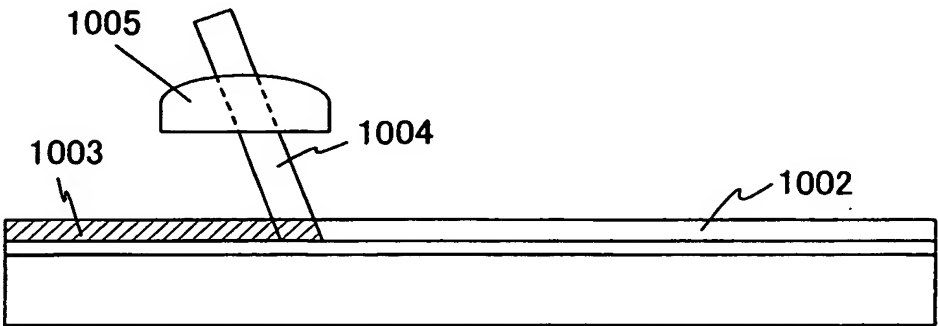


FIG. 10B

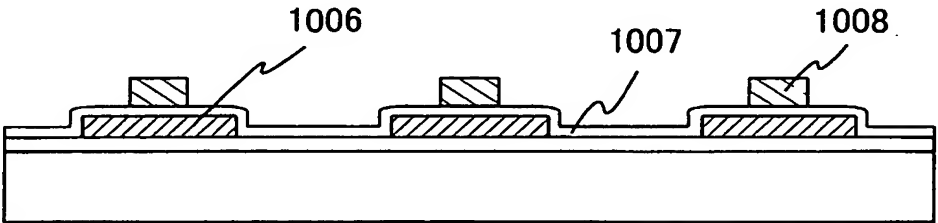


FIG. 10C

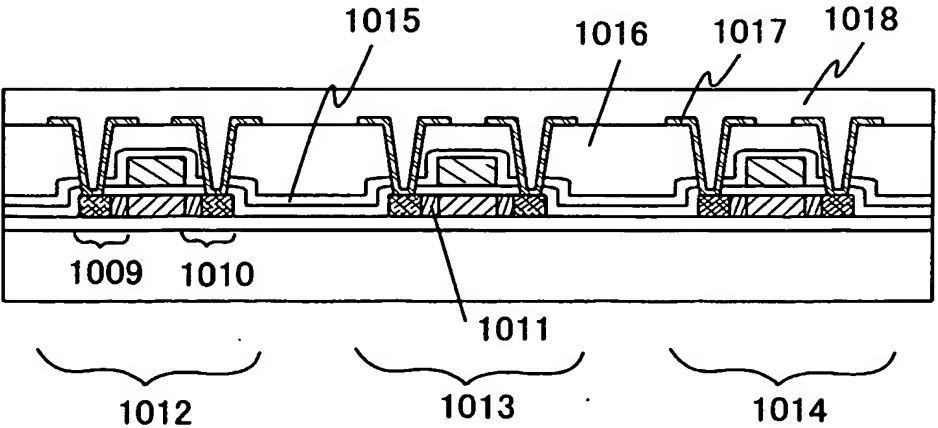
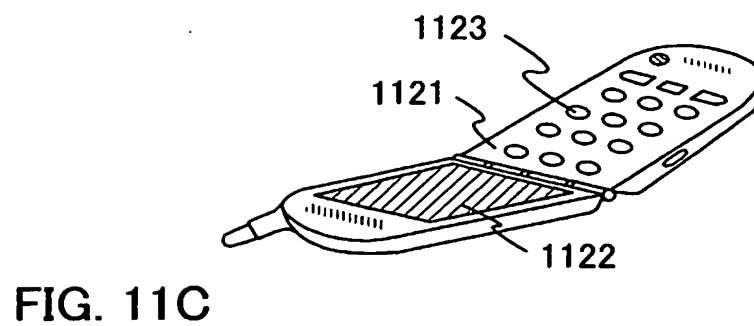
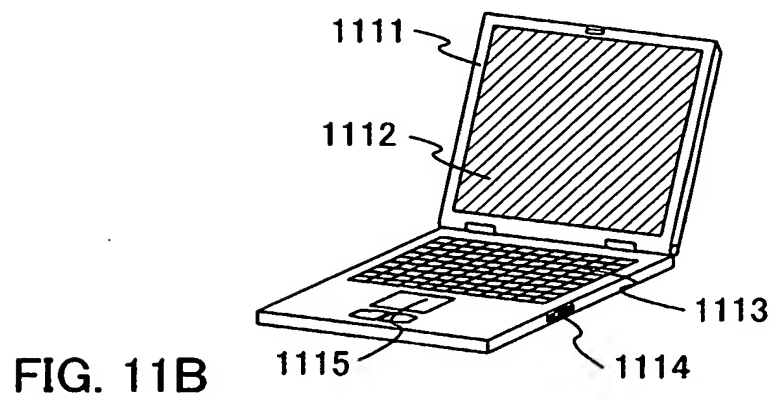
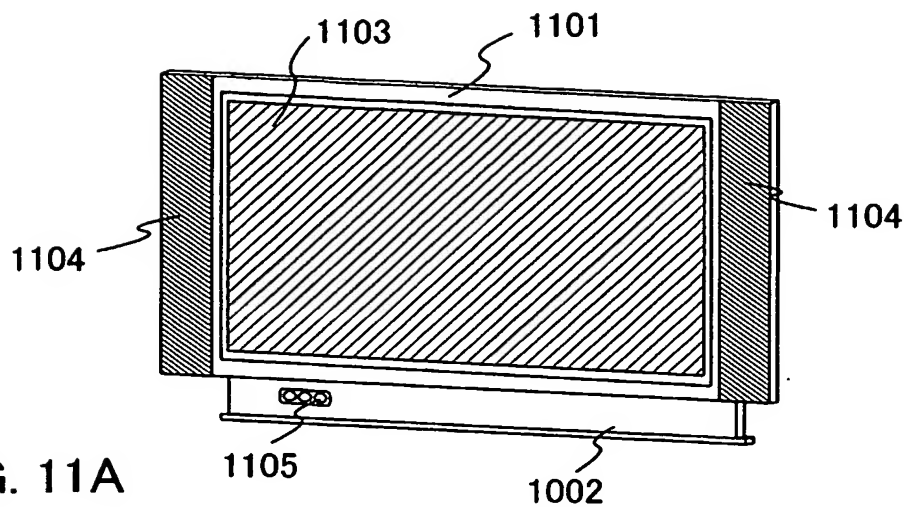


FIG. 10D

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## EXPLANATION OF REFERENCE

1: LASER OSCILLATOR, 2: CYLINDRICAL LENS ARRAY, 3: CYLINDRICAL LENS ARRAY, 4: CYLINDRICAL LENS ARRAY, 5: CYLINDRICAL LENS ARRAY, 6: CYLINDRICAL LENS ARRAY, 7: MIRROR, 8: DOUBLET CYLINDRICAL LENS, 9: IRRADIATION SURFACE, 11: LASER OSCILLATOR, 12: MIRROR, 13: CONVEX LENS, 14: BEAM, 15: IRRADIATION SURFACE, 101: LASER OSCILLATOR, 102: POLARIZING PLATE, 103: POLARIZING PLATE, 104: MIRROR, 105: CONVEX LENS, 106: NON-SINGLE CRYSTAL SEMICONDUCTOR FILM, 107: SUBSTRATE, 108: X-AXIS STAGE, 109: Y-AXIS STAGE, 110: DIFFRACTIVE OPTICAL ELEMENT, 120: BEAM, 121: INCIDENT BEAM, 1000: SUBSTRATE, 1001: BASE FILM, 1002: AMORPHOUS SEMICONDUCTOR FILM, 1003: CRYSTALLINE SEMICONDUCTOR FILM, 1005: CONVEX LENS, 1006: SEMICONDUCTOR FILM, 1007: GATE INSULATING FILM, 1008: GATE ELECTRODE, 1009: SOURCE REGION, 1010: DRAIN REGION, 1011: LDD REGION, 1012: N-CHANNEL TFT, 1013: P-CHANNEL TFT, 1014: N-CHANNEL TFT, 1015: INSULATING FILM, 1016: INSULATING FILM, 1017: WIRING, 1018: INSULATING FILM, 1101: CASE, 1102: SUPPORTING STAND, 1103: DISPLAY PORTION, 1104: SPEAKER PORTIONS, 1105: VIDEO INPUT TERMINAL, 1111: CASE, 1112: DISPLAY PORTION, 1113: KEYBOARD, 1114: EXTERNAL CONNECTION PORT, 1115: POINTING MOUSE, 1121: CASE, 1122: OPERATION KEYS, 1123: DISPLAY PORTION